

# Shigeki Sakai

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/6130668/publications.pdf>

Version: 2024-02-01

144  
papers

3,022  
citations

236925

25  
h-index

189892

50  
g-index

146  
all docs

146  
docs citations

146  
times ranked

1489  
citing authors

| #  | ARTICLE  | IF  | CITATIONS |
|----|--|-----|-----------|
| 1  | Area-Scalable 10 <sup>9</sup> -Cycle-High-Endurance FeFET of Strontium Bismuth Tantalate Using a Dummy-Gate Process. <i>Nanomaterials</i> , 2021, 11, 101.   | 4.1 | 11        |
| 2  | A time-domain analog weighted-sum calculation circuit using ferroelectric-gate field-effect transistors for artificial intelligence processors. <i>Japanese Journal of Applied Physics</i> , 2020, 59, 040604.   | 1.5 | 3         |
| 3  | Downsizing of High-Endurance and Long-Retention Pt/Ca <sub>x</sub> Sr <sub>1-x</sub> Bi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /(HfO <sub>2</sub> ) <sub>x</sub> (Al <sub>2</sub> O <sub>3</sub> ) <sub>1-x</sub> /Si FeFETs. <i>Topics in Applied Physics</i> , 2020, , 61-77.                 | 0.8 | 0         |
| 4  | Development of High-Endurance and Long-Retention FeFETs of Pt/Ca <sub>x</sub> Sr <sub>1-x</sub> Bi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /(HfO <sub>2</sub> ) <sub>x</sub> (Al <sub>2</sub> O <sub>3</sub> ) <sub>1-x</sub> /Si Gate Stacks. <i>Topics in Applied Physics</i> , 2020, , 23-60. | 0.8 | 1         |
| 5  | Novel Application of FeFETs to NAND Flash Memory Circuits. <i>Topics in Applied Physics</i> , 2020, , 319-341.   | 0.8 | 0         |
| 6  | Investigation of Ferroelectric Grain Sizes and Orientations in Pt/Ca <sub>x</sub> Sr <sub>1-x</sub> Bi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /HfAlO/Si High Performance Ferroelectric-Gate Field-Effect-Transistors. <i>Materials</i> , 2019, 12, 399.   | 2.9 | 7         |
| 7  | High-Endurance Ferroelectric NOR Flash Memory Using (Ca,Sr)Bi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> FeFETs. , 2018, , .  |     | 7         |
| 8  | Method for disclosing invisible physical properties in metal/ferroelectric/insulator/semiconductor gate stacks. <i>Journal Physics D: Applied Physics</i> , 2017, 50, 165107.  | 2.8 | 7         |
| 9  | 3.3 V write-voltage Ir/Ca <sub>0.2</sub> Sr <sub>0.8</sub> Bi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /HfO <sub>2</sub> /Si ferroelectric-gate field-effect transistors with 10 <sup>9</sup> endurance and good retention. <i>Japanese Journal of Applied Physics</i> . 2017, 56, 04CE04.        | 1.5 | 11        |
| 10 | Dynamic Analog Characteristics of 10 <sup>9</sup> Cycle-Endurance Low-Voltage Nonvolatile Ferroelectric-Gate Memory Transistors. , 2017, , .   |     | 3         |
| 11 | Precise understanding of ferroelectric properties in metal/ferroelectric/insulator/semiconductor FETs with (Ca,Sr)Bi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> . , 2017, , .   |     | 0         |
| 12 | Compact model of ferroelectric-gate field-effect transistor for circuit simulation based on multidomain Landau-Khalatnikov theory. <i>Japanese Journal of Applied Physics</i> , 2017, 56, 04CE07.  | 1.5 | 7         |
| 13 | Ferroelectric-Gate Field Effect Transistor Memories. <i>Topics in Applied Physics</i> , 2016, , .  | 0.8 | 62        |
| 14 | Novel Application of FeFETs to NAND Flash Memory Circuits. <i>Topics in Applied Physics</i> , 2016, , 271-293.   | 0.8 | 0         |
| 15 | Novel process for widening memory window of sub-200 nm ferroelectric-gate field-effect transistor by ferroelectric coating the gate-stack sidewall. <i>Semiconductor Science and Technology</i> , 2015, 30, 015024.  | 2.0 | 8         |
| 16 | 100-nm-size ferroelectric-gate field-effect transistor with 10 <sup>8</sup> -cycle endurance. <i>Japanese Journal of Applied Physics</i> , 2015, 54, 088004.   | 1.5 | 16        |
| 17 | Electrical properties of Ca <sub>x</sub> Sr <sub>1-x</sub> Bi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> ferroelectric-gate field-effect transistors. <i>Semiconductor Science and Technology</i> , 2013, 28, 085003.   |     | 14        |
| 18 | FeFET Logic Circuits for Operating A 64 kb FeNAND Flash Memory Array. <i>Integrated Ferroelectrics</i> , 2012, 132, 114-121.   | 0.7 | 15        |

| #  | ARTICLE  | IF  | CITATIONS |
|----|--|-----|-----------|
| 19 | 64 kbit Ferroelectric-Gate-Transistor-Integrated NAND Flash Memory with 7.5 V Program and Long Data Retention. Japanese Journal of Applied Physics, 2012, 51, 04DD01.  | 1.5 | 12        |
| 20 | Electrical properties of ferroelectric-gate FETs with SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> formed using MOCVD technique. Applied Physics A: Materials Science and Processing, 2012, 108, 835-842.  | 2.3 | 17        |
| 21 | Downsizing and memory array integration of Pt/SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /Hf-Al-O/Si ferroelectric-gate field-effect transistors. , 2012, , .  |     | 7         |
| 22 | 64 kbit Ferroelectric-Gate-Transistor-Integrated NAND Flash Memory with 7.5 V Program and Long Data Retention. Japanese Journal of Applied Physics, 2012, 51, 04DD01.  | 1.5 | 34        |
| 23 | Initialize and Weak-Program Erasing Scheme for High-Performance and High-Reliability Ferroelectric NAND Flash Solid-State Drive. IEICE Transactions on Electronics, 2012, E95.C, 609-616.  | 0.6 | 0         |
| 24 | 0.5V Bit-Line-Voltage Self-Boost-Programming in Ferroelectric-NAND Flash Memory. , 2011, , .   |     | 6         |
| 25 | Downsizing of Ferroelectric-Gate Field-Effect-Transistors for Ferroelectric-NAND Flash Memory Cells. , 2011, , .   |     | 13        |
| 26 | Improvement of Read Disturb, Program Disturb and Data Retention by Memory Cell VTH Optimization of Ferroelectric (Fe)-NAND Flash Memories for Highly Reliable and Low Power Enterprise Solid-State Drives (SSDs). IEICE Transactions on Electronics, 2011, E94-C, 539-547.               | 0.6 | 3         |
| 27 | A 1.0V power supply, 9.3GB/s write speed, Single-Cell Self-Boost program scheme for high performance ferroelectric NAND flash SSD. Solid-State Electronics, 2011, 58, 34-41.   | 1.4 | 7         |
| 28 | Recent Progress in Downsizing FeFETs for Fe-NAND Application. Materials Research Society Symposia Proceedings, 2011, 1337, 49.   | 0.1 | 1         |
| 29 | Recent Advances in Ferroelectric-Gate Field-Effect-Transistor Technology. Integrated Ferroelectrics, 2011, 124, 140-146.   | 0.7 | 4         |
| 30 | Large grain growth by annealing of Ag-covered Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>8</sub> + $\hat{\Gamma}$ thin films and its application in the fabrication of intrinsic Josephson junctions. Superconductor Science and Technology, 2010, 23, 115006.             | 3.5 | 7         |
| 31 | A Ferroelectric NAND Flash Memory for Low-power and Highly Reliable Enterprise SSDs and a Ferroelectric 6T-SRAM for 0.5V Low-power CPU and SoC. Materials Research Society Symposia Proceedings, 2010, 1250, 1.  | 0.1 | 0         |
| 32 | Recent Progress of Ferroelectric-Gate Field-Effect Transistors and Applications to Nonvolatile Logic and FeNAND Flash Memory. Materials, 2010, 3, 4950-4964.   | 2.9 | 66        |
| 33 | A 1.2 V Power Supply, 2.43 Times Power Efficient, Adaptive Charge Pump Circuit with Optimized Threshold Voltage at Each Pump Stage for Ferroelectric-NAND Flash Memories. Japanese Journal of Applied Physics, 2010, 49, 04DD10.   | 1.5 | 5         |
| 34 | A 0.5-V Six-Transistor Static Random Access Memory with Ferroelectric-Gate Field Effect Transistors. Japanese Journal of Applied Physics, 2010, 49, 121501.  | 1.5 | 4         |
| 35 | Fabrication and characterization of sub-0.6- $\mu\text{m}$ ferroelectric-gate field-effect transistors. Semiconductor Science and Technology, 2010, 25, 115013.  | 2.0 | 20        |
| 36 | A Negative Word-Line Voltage Negatively-Incremental Erase Pulse Scheme with $\hat{\Gamma}$ V <sub>TH</sub> = 1/6 <sup>th</sup> V <sub>ERASE</sub> for Enterprise Solid-State Drive Application Ferroelectric-NAND Flash Memories. Japanese Journal of Applied Physics, 2010, 49, 04DD08. | 1.5 | 5         |

| #  | ARTICLE  | IF  | CITATIONS |
|----|--|-----|-----------|
| 37 | Lowered operation voltage in Pt/SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /HfO <sub>2</sub> /Si ferroelectric-gate field-effect transistors by oxynitriding Si. Semiconductor Science and Technology, 2010, 25, 055005.   | 2.0 | 29        |
| 38 | A 1.0V power supply, 9.5GByte/sec write speed, Single-Cell Self-Boost program scheme for Ferroelectric NAND Flash SSD. , 2010, , .   |     | 10        |
| 39 | Ferroelectric (Fe)-NAND Flash Memory With Batch Write Algorithm and Smart Data Store to the Nonvolatile Page Buffer for Data Center Application High-Speed and Highly Reliable Enterprise Solid-State Drives. IEEE Journal of Solid-State Circuits, 2010, 45, 2156-2164. | 5.4 | 18        |
| 40 | Memory window widening of Pt/SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /HfO <sub>2</sub> /Si ferroelectric-gate field-effect transistors by nitriding Si. Semiconductor Science and Technology, 2009, 24, 105026.   | 2.0 | 19        |
| 41 | Threshold voltage adjustment of ferroelectric-gate field effect transistors by ion implantation. Semiconductor Science and Technology, 2009, 24, 025012.   | 2.0 | 25        |
| 42 | Operational method of a ferroelectric (Fe)-NAND flash memory array. Semiconductor Science and Technology, 2009, 24, 105029.  | 2.0 | 32        |
| 43 | A zero V <sub>TH</sub> memory cell ferroelectric-NAND flash memory with 32% read disturb, 24% program disturb, 10% data retention improvement for enterprise SSD. , 2009, , .  |     | 7         |
| 44 | A 0.5V operation, 32% lower active power, 42% lower leakage current, ferroelectric 6T-SRAM with V <sub>TH</sub> self-adjusting function for 60% larger Static Noise Margin. , 2009, , .  |     | 8         |
| 45 | Fabrication of thin-film-type Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>8</sub> + <i>n</i> intrinsic Josephson junctions by pulsed-laser-deposition. Superconductor Science and Technology, 2009, 22, 125004.   | 3.5 | 10        |
| 46 | FeCMOS logic inverter circuits with nonvolatile-memory function. IEICE Electronics Express, 2009, 6, 831-836.  | 0.8 | 17        |
| 47 | Threshold-voltage distribution of Pt/SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /HfAlO/Si MFIS FETs. Semiconductor Science and Technology, 2008, 23, 045011.   | 2.0 | 20        |
| 48 | Highly Scalable Fe(Ferroelectric)-NAND Cell with MFIS(Metal-Ferroelectric-Insulator-Semiconductor) Structure for Sub-10nm Tera-Bit Capacity NAND Flash Memories. , 2008, , .   |     | 30        |
| 49 | Basic operation of novel ferroelectric CMOS circuits. Electronics Letters, 2008, 44, 467.  | 1.0 | 27        |
| 50 | Millimeter-wave radiation from a Teflon dielectric probe and its imaging application. Measurement Science and Technology, 2008, 19, 115501.  | 2.6 | 13        |
| 51 | Optimum ambient N <sub>2</sub> pressure during HfAlO pulsed-laser deposition in Pt <sup>*</sup> •SBT <sup>*</sup> •HfAlO <sup>*</sup> •Si field effect transistors. Journal of Vacuum Science & Technology B, 2008, 26, 1585.  | 1.3 | 10        |
| 52 | Effect of Nitrogen Inclusion into Hf-Al-O Layer on Device Properties of Pt/SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /Hf-Al-O/Si Diodes. Funtai Oyobi Fumatsu Yakin/Journal of the Japan Society of Powder and Powder Metallurgy, 2008, 55, 17-20.                | 0.2 | 6         |
| 53 | Low-magnetic-field operations of intrinsic Josephson junctions with a long-axis periodicity by artificial critical-current modulations. Superconductor Science and Technology, 2007, 20, S79-S86.  | 3.5 | 0         |
| 54 | Large-area pulsed-laser deposition of dielectric and ferroelectric thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2007, 25, 903-907.  | 2.1 | 29        |

| #  | ARTICLE  | IF  | CITATIONS |
|----|--|-----|-----------|
| 55 | Statistical Threshold-Voltage Distribution and Elevated-Temperature Operations of Pt/SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /Hf-Al-O/Si MFIS FETs. Applications of Ferroelectrics, IEEE International Symposium on, 2007, , .  | 0.0 | 0         |
| 56 | Characterization of Pt-SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> -Hf-Al-O-Si field-effect transistors at elevated temperatures. Applied Physics Letters, 2006, 89, 222910.  | 3.3 | 50        |
| 57 | Leakage current of multiferroic (Bi <sub>0.6</sub> Tb <sub>0.3</sub> La <sub>0.1</sub> )FeO <sub>3</sub> thin films grown at various oxygen pressures by pulsed laser deposition and annealing effect. Journal of Applied Physics, 2006, 99, 054104.   | 2.5 | 165       |
| 58 | The fabrication and electrical properties of critical-current-modulated intrinsic Josephson junctions in Bi <sub>2</sub> Sr <sub>2</sub> Ca <sub>1-y</sub> YCu <sub>2</sub> O <sub>x</sub> /Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> stacks. Superconductor Science and Technology, 2006, 19, 459-461. | 3.5 | 1         |
| 59 | Gate Materials and Fabrication-Processes of Metal-Ferroelectric-Insulator-Semiconductor Memory FETs with Long Data Retention. Advances in Science and Technology, 2006, 45, 2382.  | 0.2 | 3         |
| 60 | Properties of a dielectric probe for scanning near-field millimeter-wave microscopy. Journal of Applied Physics, 2006, 99, 056105.   | 2.5 | 9         |
| 61 | Face-to-face annealing of Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> thin films for intrinsic Josephson junctions with uniform critical currents. Physica C: Superconductivity and Its Applications, 2005, 426-431, 1474-1478.   | 1.2 | 12        |
| 62 | Self-Aligned-Gate Metal/Ferroelectric/Insulator/Semiconductor Field-Effect Transistors with Long Memory Retention. Japanese Journal of Applied Physics, 2005, 44, L800-L802.   | 1.5 | 114       |
| 63 | Theoretical and numerical study on multistacked Josephson junctions with a parametric modulation of their critical currents. Physical Review B, 2005, 72, .  | 3.2 | 3         |
| 64 | Growth of High-Quality Single-Phase Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> Whiskers by a New Growth-Melt-Regrowth Method. Japanese Journal of Applied Physics, 2004, 43, 3378-3380.  | 1.5 | 4         |
| 65 | Pt/SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> /Hf-Al-O/Si Field-Effect-Transistor with Long Retention Using Unsaturated Ferroelectric Polarization Switching. Japanese Journal of Applied Physics, 2004, 43, 7876-7878.  | 1.5 | 54        |
| 66 | Fabrication and electrical properties of ferroelectric-gate FETS with epitaxial gate structures. Electronics and Communications in Japan, 2004, 87, 24-33.   | 0.2 | 0         |
| 67 | Resonant characteristics of twofold Josephson junctions with various critical current ratio. Physica C: Superconductivity and Its Applications, 2004, 412-414, 1468-1472.  | 1.2 | 4         |
| 68 | Characteristics of intrinsic Josephson junctions using a Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> thin film estimated overall in a chip. Physica C: Superconductivity and Its Applications, 2004, 412-414, 1410-1413.  | 1.2 | 5         |
| 69 | Composition analysis of modified layer in YBCO trilayer interface-engineered Josephson junctions. Physica C: Superconductivity and Its Applications, 2004, 412-414, 1419-1423.   | 1.2 | 0         |
| 70 | Temperature dependence of composition ratio of Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>8+y</sub> film by PLD method. Physica C: Superconductivity and Its Applications, 2004, 412-414, 1354-1357.   | 1.2 | 20        |
| 71 | Metal-Ferroelectric-Insulator-Semiconductor Memory FET With Long Retention and High Endurance. IEEE Electron Device Letters, 2004, 25, 369-371.  | 3.9 | 200       |
| 72 | Unified theory for magnetic and electric field coupling in multistacked Josephson junctions. Physical Review B, 2004, 70, .  | 3.2 | 33        |

| #  | ARTICLE   | IF  | CITATIONS |
|----|---|-----|-----------|
| 73 | Memory properties of a ferroelectric gate field-effect transistor with an adjoining metal-ferroelectric-metal assistance cell. Journal of Applied Physics, 2003, 94, 2559-2562.   | 2.5 | 14        |
| 74 | Growth of Single Phase Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> Whiskers Using Optimized Starting Compositions for Glassy Precursors. Japanese Journal of Applied Physics, 2003, 42, 5022-5023.   | 1.5 | 4         |
| 75 | Super-relativistic fluxon in a Josephson multilayer: Experiment and simulation. Physical Review B, 2002, 66, .  | 3.2 | 30        |
| 76 | Flux-flow cavity resonance modes in intrinsic Josephson junctions by Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> thin films. Physica C: Superconductivity and Its Applications, 2002, 367, 404-409.  | 1.2 | 9         |
| 77 | Growth and characterization of potassium tantalate niobate single crystals by the step-cooling technique. Journal of Crystal Growth, 2002, 237-239, 694-699.  | 1.5 | 9         |
| 78 | Description of intrinsic Josephson junctions by the inductive coupling theory. Physica C: Superconductivity and Its Applications, 2001, 362, 1-9.   | 1.2 | 3         |
| 79 | Fabrication and critical currents of thin-film-type Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> intrinsic Josephson junctions. Physica C: Superconductivity and Its Applications, 2001, 362, 256-260.  | 1.2 | 10        |
| 80 | Fabrication and Electrical Characteristics of a Trench-Type Metal-Ferroelectric-Metal-Insulator-Semiconductor Field Effect Transistor. Japanese Journal of Applied Physics, 2001, 40, 5605-5609.  | 1.5 | 1         |
| 81 | Epitaxial structure SrTiO <sub>3</sub> on Si. Journal of Applied Physics, 2001, 89, 5421-5424.  | 2.5 | 21        |
| 82 | All-perovskite-oxide ferroelectric memory transistor composed of Bi <sub>2</sub> Sr <sub>2</sub> CuO <sub>x</sub> and PbZr <sub>0.5</sub> Ti <sub>0.5</sub> O <sub>3</sub> films. Journal of Applied Physics, 2001, 89, 8153-8158.  | 2.5 | 13        |
| 83 | Epitaxial structure SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> / SrTiO <sub>3</sub> / Ce <sub>0.12</sub> Zr <sub>0.88</sub> O <sub>2</sub> / Si for ferroelectric-gate FET memory. Integrated Ferroelectrics, 2001, 40, 135-143.  | 0.7 | 5         |
| 84 | Plasma resonance and flux dynamics in layered high-T <sub>c</sub> superconductors. Physica C: Superconductivity and Its Applications, 2000, 332, 297-301.   | 1.2 | 3         |
| 85 | Epitaxial Growth of Bi <sub>4</sub> Ti <sub>3</sub> O <sub>12</sub> /CeO <sub>2</sub> /Ce <sub>0.12</sub> Zr <sub>0.88</sub> O <sub>2</sub> and Bi <sub>4</sub> Ti <sub>3</sub> O <sub>12</sub> /SrTiO <sub>3</sub> /Ce <sub>0.12</sub> Zr <sub>0.88</sub> O <sub>2</sub> Thin Films on Si and Its Application to Metal-Ferroelectric-Insulator-Semiconductor Diodes. Japanese Journal of Applied Physics, 2000, 39, 5505-5511. | 1.5 | 6         |
| 86 | Prediction of half harmonic generation in stacked Josephson junctions and Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> single crystals. Physical Review B, 2000, 61, 11328-11331.   | 3.2 | 4         |
| 87 | Growth Style of Bi <sub>4</sub> Ti <sub>3</sub> O <sub>12</sub> Thin Films on CeO <sub>2</sub> /Ce <sub>0.12</sub> Zr <sub>0.88</sub> O <sub>2</sub> Buffered Si Substrates. Japanese Journal of Applied Physics, 1999, 38, 5411-5416.  | 1.5 | 10        |
| 88 | Interaction induced by nonuniform self-fields in stacks of two long Josephson junctions. IEEE Transactions on Applied Superconductivity, 1999, 9, 3953-3956.  | 1.7 | 0         |
| 89 | Memory properties of SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> thin films prepared on SiO <sub>2</sub> /Si substrates. Applied Physics Letters, 1999, 75, 1613-1615.   | 3.3 | 61        |
| 90 | Plasma resonance in anisotropic layered high-T <sub>c</sub> superconductors. Physical Review B, 1999, 60, 9810-9816.  | 3.2 | 14        |

| #   | ARTICLE   | IF  | CITATIONS |
|-----|---|-----|-----------|
| 91  | Particle-free superconducting Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>x</sub> ultrathin films prepared by atomic-layer-controlled molecular beam epitaxy technique. <i>Physica C: Superconductivity and Its Applications</i> , 1999, 311, 42-48. | 1.2 | 14        |
| 92  | Epitaxial Bi <sub>4</sub> Ti <sub>3</sub> O <sub>12</sub> thin film growth using Bi self-limiting function. <i>Journal of Crystal Growth</i> , 1999, 200, 161-168.  | 1.5 | 24        |
| 93  | Pulsed laser deposition and ferroelectric properties of SrBi <sub>2</sub> Ta <sub>2</sub> O <sub>9</sub> thin films. <i>Materials Letters</i> , 1999, 38, 406-412.  | 2.6 | 12        |
| 94  | Josephson plasma resonance in superconducting multilayers. <i>Physical Review B</i> , 1998, 58, 2820-2826.  | 3.2 | 43        |
| 95  | Dynamics of multiple-junction stacked flux-flow oscillators: Comparison between theory and experiment. <i>Physical Review B</i> , 1998, 58, 5777-5782.  | 3.2 | 23        |
| 96  | Submillimeter-band high-power generation using multilayered Josephson junctions. <i>Applied Physics Letters</i> , 1998, 73, 686-688.  | 3.3 | 57        |
| 97  | Maximum supercurrent in two Josephson-junction stacks: Theory and experiment. <i>Physical Review B</i> , 1998, 58, 6497-6505.   | 3.2 | 9         |
| 98  | Bunched fluxon states in one-dimensional Josephson-junction arrays. <i>Physical Review B</i> , 1998, 57, 11691-11697.   | 3.2 | 38        |
| 99  | Molecular beam epitaxial growth of BSCCO and Bi-based oxides: self-limiting growth of the Bi element. , 1998, , .   |     | 0         |
| 100 | Self-limiting process for the bismuth content in molecular beam epitaxial growth of Bi <sub>2</sub> Sr <sub>2</sub> CuO <sub>y</sub> thin films. <i>Applied Physics Letters</i> , 1997, 71, 3712-3714.  | 3.3 | 36        |
| 101 | Atomic absorption spectroscopy system for flux monitoring and atomic-layer control of molecular beam epitaxial growth of BiSrCaCuO. <i>Review of Scientific Instruments</i> , 1997, 68, 2850-2855.  | 1.3 | 22        |
| 102 | Nanometer level etching and deposition of Bi-Sr-Ca-Cu-O superconducting thin films. , 1996, , .   |     | 4         |
| 103 | Digital laser etching of Bi-Sr-Ca-Cu-O superconducting thin films. <i>Thin Solid Films</i> , 1996, 281-282, 513-516.  | 1.8 | 1         |
| 104 | Molecular beam epitaxial growth of SrO and CaO with RHEED intensity oscillation. <i>Journal of Low Temperature Physics</i> , 1996, 105, 1337-1342.  | 1.4 | 13        |
| 105 | A Digital Method of Gas Laser Etching for Oxide Superconductors. <i>Japanese Journal of Applied Physics</i> , 1996, 35, L94-L96.  | 1.5 | 4         |
| 106 | Numerical study of fluxon dynamics in a system of two stacked Josephson junctions. <i>Journal of Applied Physics</i> , 1995, 77, 1171-1177.   | 2.5 | 37        |
| 107 | Dynamic behavior of Josephson-coupled layered structures. <i>Physical Review B</i> , 1994, 50, 3942-3952.   | 3.2 | 205       |
| 108 | Electric-field effects in metal-insulator-superconductor diodes: possibility of singularity in capacitance-voltage relationships. <i>Physica B: Condensed Matter</i> , 1994, 194-196, 2399-2400.  | 2.7 | 0         |

| #   | ARTICLE  | IF  | CITATIONS |
|-----|--|-----|-----------|
| 109 | Theory and experiment on electromagnetic-wave-propagation velocities in stacked superconducting tunnel structures. <i>Physical Review B</i> , 1994, 50, 12905-12914.   | 3.2 | 154       |
| 110 | Fluxons in thin-film superconductor-insulator superlattices. <i>Journal of Applied Physics</i> , 1993, 73, 2411-2418.  | 2.5 | 391       |
| 111 | Theoretical study of electric-field effects in high-Tc oxide superconductors using an ultrathin-metal-insulator superlattice model. <i>Physical Review B</i> , 1993, 47, 9042-9047.  | 3.2 | 20        |
| 112 | Molecular Beam Epitaxy Fabrication of SrTiO <sub>3</sub> and Bi <sub>2</sub> Sr <sub>2</sub> CaCu <sub>2</sub> O <sub>8</sub> Heterostructures Using a Novel Reflection High-Energy Electron Diffraction Monitoring Technique. <i>Japanese Journal of Applied Physics</i> , 1992, 31, L949-L952. | 1.5 | 23        |
| 113 | RHEED Intensity Monitored Growth of Bi-Sr-Ca-Cu-O Superconductors. <i>Japanese Journal of Applied Physics</i> , 1992, 31, L399-L401.   | 1.5 | 11        |
| 114 | Rheed Intensity Monitored Growth of Bi-Sr-Ca-Cu-O Superconductors. <i>Materials Research Society Symposia Proceedings</i> , 1992, 275, 73.   | 0.1 | 3         |
| 115 | Atomic layer by atomic layer growth of Bi-Sr-Ca-Cu oxide superconducting thin films by molecular beam epitaxy. <i>Physica C: Superconductivity and Its Applications</i> , 1991, 185-189, 2013-2014.  | 1.2 | 4         |
| 116 | In-situ growth of Bi-Sr-Ca-Cu oxide superconducting thin films by molecular beam epitaxy with a pure ozone source. <i>Journal of Crystal Growth</i> , 1991, 115, 758-761.  | 1.5 | 12        |
| 117 | Laser Etching of Bi-Sr-Ca-Cu-O Superconducting Thin Films. <i>Japanese Journal of Applied Physics</i> , 1991, 30, L355-L357.   | 1.5 | 2         |
| 118 | In-Situ Growth of Bi-Sr-Ca-Cu-O Thin Films by Molecular Beam Epitaxy. , 1991, , 1085-1088.   |     | 1         |
| 119 | Analytic solutions for bunched two-fluxon states in Josephson transmission lines. <i>Physical Review B</i> , 1987, 36, 812-814.  | 3.2 | 6         |
| 120 | Direct observation of fluxon reflection in a Josephson transmission line. <i>Physical Review B</i> , 1987, 35, 5357-5360.  | 3.2 | 17        |
| 121 | Perturbation analysis of a parametrically changed sine-Gordon equation. <i>Physical Review B</i> , 1987, 36, 217-225.  | 3.2 | 25        |
| 122 | Criteria for fluxon generation in long Josephson junctions by current pulses. <i>Applied Physics Letters</i> , 1987, 50, 1107-1109.  | 3.3 | 7         |
| 123 | Analytical and numerical results for a long Josephson junction with surface losses. <i>IEEE Transactions on Magnetics</i> , 1987, 23, 1114-1117.   | 2.1 | 4         |
| 124 | Bunching of Solitons in Long Josephson Junctions. <i>Japanese Journal of Applied Physics</i> , 1987, 26, 1579.   | 1.5 | 7         |
| 125 | Reflection Properties of Fluxon in a Josephson Transmission Line. <i>Japanese Journal of Applied Physics</i> , 1987, 26, 1573.   | 1.5 | 0         |
| 126 | Measurements of the high frequency loss near the plasma resonance in Josephson tunnel junctions. <i>IEEE Transactions on Magnetics</i> , 1987, 23, 1118-1121.  | 2.1 | 0         |



| #   | ARTICLE  | IF  | CITATIONS |
|-----|--|-----|-----------|
| 127 | Analytic solution for fluxons in a long Josephson junction with surface losses. Physical Review B, 1986, 34, 3506-3509.  | 3.2 | 17        |
| 128 | Real time fluxon dynamics in Josephson transmission line. IEEE Transactions on Magnetics, 1985, 21, 737-740.   | 2.1 | 31        |
| 129 | Fluxon Transfer Device. Japanese Journal of Applied Physics, 1985, 24, L771-L773.  | 1.5 | 13        |
| 130 | Fluxon Divider. Japanese Journal of Applied Physics, 1985, 24, L749-L751.  | 1.5 | 3         |
| 131 | Fluxon Feedback Oscillator. Japanese Journal of Applied Physics, 1984, 23, L610-L612.  | 1.5 | 19        |
| 132 | Fluxon Devices. , 1984, , .  |     | 0         |
| 133 | A Direct Coupled Josephson Sampler. Japanese Journal of Applied Physics, 1983, 22, L435-L437.  | 1.5 | 23        |
| 134 | Fluxon Observation Using a Josephson Sampler. Japanese Journal of Applied Physics, 1983, 22, L479-L481.  | 1.5 | 20        |
| 135 | Analytical Solutions of Traveling Fluxon Waves on a Josephson Transmission Line with Shunt Conductance and Uniform Bias Current. Japanese Journal of Applied Physics, 1983, 22, 1374-1381.                     | 1.5 | 17        |
| 136 | Travelling Waves on a Josephson Transmission Line. Japanese Journal of Applied Physics, 1983, 22, 161-170.   | 1.5 | 8         |
| 137 | Fluxon Waves on a Josephson Transmission Line. Japanese Journal of Applied Physics, 1982, 21, L7-L9.   | 1.5 | 5         |
| 138 | Quasiparticle-Injected Superconducting Weak Link Device. Japanese Journal of Applied Physics, 1982, 21, 331.   | 1.5 | 3         |
| 139 | Static characteristic of a new quasiparticle injected superconducting weak link device. Electronics Letters, 1981, 17, 501.  | 1.0 | 5         |
| 140 | Quasiparticle-Injected Superconducting Weak Link Device. , 1981, , .   |     | 2         |
| 141 | Nb/GaAs super-Schottky diode. IEEE Electron Device Letters, 1980, 1, 236-238.  | 3.9 | 6         |
| 142 | Energy band of ternary alloy semiconductorsâ€”Calculation by a coherentâ€”potential approximation based on the method of linear combination of bond orbitals. Journal of Applied Physics, 1979, 50, 4143-4155. | 2.5 | 15        |
| 143 | Optical Properties of Vacuum-Deposited CdCr <sub>2</sub> Se <sub>4</sub> Thin Film. Japanese Journal of Applied Physics, 1976, 15, 2023-2024.  | 1.5 | 10        |
| 144 | Long-retention ferroelectric-gate FET with a (HfO <sub>2</sub> ) <sub>x</sub> (Al <sub>2</sub> O <sub>3</sub> ) <sub>1-x</sub> buffer-insulating layer for 1T FeRAM. , 0, , .                                  |     | 8         |